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**\*\* CONTINUING DATA \*\*\*\*\***  
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35 USC 119 (a-d) conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance	Verified and Acknowledged <i>[Signature]</i> Examiner's Signature	Initials SJL		

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**TITLE**  
 Chemically amplified positive photo resist composition and method for forming resist pattern